EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S2	7	((($4lithograph$4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and ((attach$4 or detach$4) near4 (system or apparatus or mechanism)) and (liquid near3 repellent)).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 13:41
S4	3	S3 and (($4lithograph $4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and ((attach$4 or detach$4) near4 (system or apparatus or mechanism)) and (liquid near3 repellent)).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 13:48
S3	420	(hiroyuki near3 nagasaka).inv. or (hiroaki near3 takaiwa). inv. or (ryuichi near3 hoshika).inv.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 13:48
S5	2	((($4lithograph$4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and ((attach$4 or detach$4) near4 (system or apparatus or mechanism)) and ((liquid near3 repellent) near5 (stage or base or support $4))).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 13:49

S7	2	(($4lithograph$4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and (sensor or detector) and ((attach$4 or detach$4) near4 (system or apparatus or mechanism)) and ((liquid near3 repellent) near5 (stage or base or support$4 or hold$4))).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 13:51
S6	3	(($4lithograph$4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and (flat near3 surface) and ((attach$4 or detach$4) near4 (system or apparatus or mechanism)) and ((liquid near3 repellent) near5 (stage or base or support$4 or hold$4))).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 13:51
S8	1	(($4lithograph$4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and (adhesive) and ((attach$4 or detach$4) near4 (system or apparatus or mechanism)) and ((liquid near3 repellent) near5 (stage or base or support$4 or hold$4))).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 13:52
S9	1	(($4lithograph$4 or exposure) and (projection adj3 (lens or system or apparatus or device)) and ((liquid near3 repellent) near4 (exchang$4 or detach$4)) and (exchang$4 near5 tim$4)).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 13:54

S10	0	(($4lithograph$4 or exposure) and (((liquid or fluid or immersion) near4 (wafer or substrate)) and (((liquid near3 repellent) near4 (judge $4 or determin$4)) same (amount or intensity) near4 (light or radiation or illumination))).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 14:18
S11	1	(($4lithograph$4 or exposure) and (((liquid near3 repellent) near3 (exchang$4)) and ((reference adj3 (member or plate)) near4 (liquid near3 repellent))).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/02/23 14:21
S14	272	("20020074635" | "20020163629" | "20030030916" | "20030066975" | "20030139620" | "20030174408" | "20040000627" | "20040075895" | "20040109237" | "20040114117" | "20040118184" | "20040119954" | "20040125351" | "20040136494" | "20040160582" | "20040165159" | "20040169834" | "20040169924" | "20040180294" | "20040180299" | "20040207824" | "20040211920" | "20040224265" | "20040224525" | "20040227923" | "20040233405" | "20040253547" | "20040253548" | "20040257544" | "20040259008" | "20040259040" | "20040263808" | "20040263809" |	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/19 14:52

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L2	0	((($4lithograph$4 or exposure) and (((liquid or fluid or immersion) near4 (wafer or substrate)) and ((((liquid near3 repellent) near4 (judge$4 or determin$4)) same (amount or intensity) near4 (light or radiation or illumination))).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/19 22:10
L3	440	(hiroyuki near3 nagasaka).inv. or (hiroaki near3 takaiwa). inv. or (ryuichi near4 hoshika).inv.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/19 22:11
L4	1	3 and ((($4lithograph$4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and (sensor or detector) and ((attach $4 or detach$4) near4 (system or apparatus or mechanism)) and ((liquid near3 repellent) near5 (stage or base or support$4 or hold$4))).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/19 22:15
L6	3	((($4lithograph$4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and (flat near3 surface) and ((attach $4 or detach$4) near4 (system or apparatus or mechanism)) and ((liquid near3 repellent) near5 (stage or base or support$4 or hold$4))).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/19 22:17

| L7 | 1 | ((($4lithograph$4 or exposure) and (projection adj5 (lens or system or apparatus or device)) and ((liquid near3 repellent) near4 (exchang$4 or detach $4)) and (exchang$4 near5 tim$4)).clm. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/06/19 22:19 |

EAST Search History (Interference)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S12	2	"3" and (($4lithograph $4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and ((attach$4 or detach$4) near4 (system or apparatus or mechanism)) and ((liquid near3 repellent) near5 (stage or base or support $4))).clm.	US-PGPUB; USPAT; UPAD	OR	ON	2011/02/23 13:50
S13	1	"3" and (($4lithograph $4 or exposure) and ((liquid near3 repellent) near3 (exchang$4)) and ((reference adj3 (member or plate)) near4 (liquid near3 repellent))).clm.	US-PGPUB; USPAT; UPAD	OR	ON	2011/02/23 14:22
S15	1	((($4lithograph$4 or exposure) and ((liquid near3 repellent) near3 (exchang$4)) and ((reference adj3 (member or plate)) near4 (liquid near3 repellent))).clm.	US-PGPUB; USPAT; UPAD	OR	ON	2011/06/19 14:58

| L1 | 0 | (($4lithograph$4 or exposure) and ((liquid or fluid or immersion) near4 (wafer or substrate)) and (((liquid near3 repellent) near4 (judge $4 or determin$4)) same (amount or intensity) near4 (light or radiation or illumination))).clm. | US-PGPUB; USPAT; UPAD | OR | ON | 2011/06/19 22:09 |
| L5 | 3 | (($4lithograph$4 or exposure) and ((immersion or liquid or fluid) near5 (substrate or wafer)) and (flat near3 surface) and ((attach $4 or detach$4) near4 (system or apparatus or mechanism)) and ((liquid near3 repellent) near5 (stage or base or support$4 or hold$4))).clm. | US-PGPUB; USPAT; UPAD | OR | ON | 2011/06/19 22:15 |

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